

**AMENDMENTS TO THE ABSTRACT:**

Please amend the abstract as follows:

**--ABSTRACT**

**THIN LAYER OF HAFNIUM OXIDE AND DEPOSIT PROCESS**

--A thin layer of hafnium oxide or stacking of thin layers comprising hafnium oxide layers for producing surface treatments of optical components, or optical components, ~~characterised in that- in which~~ at least one layer of hafnium oxide is in amorphous form ~~with and has~~ a density less than 8 gm/cm<sup>3</sup>. The invention also relates to a process for producing a ~~layer of amorphous hafnium oxide on a substrate, characterised in that the deposit is carried out~~ The layer is formed by depositing on a substrate without energy input to the substrate.

[Figure 1]

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